

# EuroNanoLab Dry Etch Expert School

9-12 April 2024, Twente

<b>TUESDAY (9<sup>th</sup> April)</b>		
<b>Timing</b>	<b>Course title</b>	<b>Speaker</b>
09:00	Registration with coffee/tea	
09:30	<i>Welcome to Twente</i>	Rob Legtenberg (MESA+ Institute for Nanotechnology)
09:45	<i>Euronanolab organization</i>	Vittorio Morandi (EuroNanoLab)
10:00	<i>Beyond Bosch-based etching, from Bosch to DREM, to DREAM, to CORE, to microCORE – Part 1</i>	Henri Jansen (DTU)
11:00	Coffee break	
11:30	<i>Beyond Bosch-based etching, from Bosch to DREM, to DREAM, to CORE, to microCORE – Part 2</i>	Henri Jansen (DTU)
13:00	Lunch buffet	
14:00	<i>The multi-scale etching approach (plasma model, sheath model and surface model)</i>	Ahmed Rhallabi (University of Nantes)
16:00	Coffee break	
16:30	<i>Process Control for III-V Compound Semiconductors Etching using Inductively-Coupled Plasma (ICP) RIE</i>	Tomoya Sugahara (SAMCO)
17:10	<i>Vapour-phase etching (vapour HF and XeF<sub>2</sub>) at nanoscale</i>	Tony O'Hara and Toni Sandbrink-Koblenz (Memsstar)
19:00	School dinner	
<b>WEDNESDAY (10<sup>th</sup> April)</b>		
08:30	Walk-in with coffee/tea	
09:00	<i>Deep reactive ion etching of ultralow expansion glasses and glass-ceramics in a fluorine-based plasma (for microsystems applications)</i>	Christoph Weigel (Technische Universität Ilmenau, Institute of Micro- and Nanotechnologies)
11:00	Coffee break	
11:30	<i>Etching silicon, dielectrics, low-k materials and ALE with plasma cryogenic</i>	Thomas Tillocher (Gremi)
13:00	Lunch buffet	
14:00	<i>Advanced HDRF technology</i>	Marc Segers (Plasma-Therm)
15:30	Coffee break	
15:45	Flash presentations	
17:00	Network, poster, and exhibition session with walking dinner	
<b>THURSDAY (11<sup>th</sup> October)</b>		
08:30	Walk-in with coffee/tea	
09:00	<i>Exhaust gas treatment solutions for semiconductor processes – focus on etch applications</i>	Jens Baßfeld (CS Clean Solutions)
10:00	<i>High Global Warming Gases Abatement using Plasma Technology</i>	Hervé Dulphy (Air Liquide)
11:00	Coffee break	
11:30	<i>Towards carbon neutrality from the perspective of a Sub-Fab solution provider</i>	Thomas Kraus (Centrotherm Clean Solutions)
12:30	<i>Corner Lithography and dry etching</i>	Niels Tas & Erwin Berenschot (MESA+ Institute for Nanotechnology)
13:30	Lunch	
14:30	<i>Atomic Layer Etching: trends and applications</i>	Erwin Kessels (TU/e)
15:30	<i>Atomic Layer Etching: tool aspects and process examples</i>	Harm Knoops (Oxford Instruments Plasma Technology)
16:30	Coffee break	
17:00	<i>Green alternatives for DRIE</i>	Henri Jansen (DTU)

18:00	Free time	
<b>FRIDAY (12<sup>th</sup> October)</b>		
08:30	Walk-in with coffee/tea	
09:00	<i>Sub-micronic etching using pulsing mode</i>	Maxime Darnon (Hubert Curien Laboratory)
10:30	Coffee break	
11:00	<i>The use of SPC DRIE process</i>	Christian Bruinink (MESA+ Institute for Nanotechnology)
12:30	Lunch buffet	

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